

HEUCOPHOS® ZCP-PLUS

in styrene-acrylic dispersion



Water based

Heubach formulation No. 319-03

08/03

FUNCTION	PRODUCT	PRODUCER	PBW
Styrene-acrylic dispersion	Acronal S 760, 50%	BASF	42.65
Defoamer	Byk-022	Byk-Chemie	0.25
Mix.			
	Water		6.35
Wetting agent	Lutensit A-EP	BASF	0.07
Neutralizing agent	Ammonia, conc.		1.20
Premix and add while mixing.			
Glycol ether	Solvenon PP	BASF	0.78
Solvent	Exxsol D 60	Exxon	0.70
Add while mixing.			
Anticorrosive pigment	HEUCOPHOS® ZCP-PLUS	Heubach	8.20
Calcium carbonate	Millicarb BG	Omya	10.55
Iron oxide red	Bayferrox 130 M	Bayer	7.80
Grind.			
Styrene-acrylic dispersion	Acronal S 760, 50%	BASF	18.05
Defoamer	Byk-022	Byk-Chemie	0.20
Add to the grind.			
Flash-rust inhibitor	Corrosion inhibitor L 1	Erbslöh	0.20
	Water		0.20
Premix and add while mixing.			
PU-thickener	Collacral PU 85	BASF	0.20
Glycol ether	Butyl glycol		1.60
Premix and add while mixing.			
Glycol ether	Butyl glycol		1.00
Add while mixing. Adjust pH 9.0 - 9.5 with ammonia.			

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FUNCTION	PRODUCT	PRODUCER	PBW
			100.00
SPECIFICATIONS			
PVC in %			22.2
Vol.-% Anticorrosive pigment reg. pigment/filler			30.0
PVC / CPVC			0.4

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